

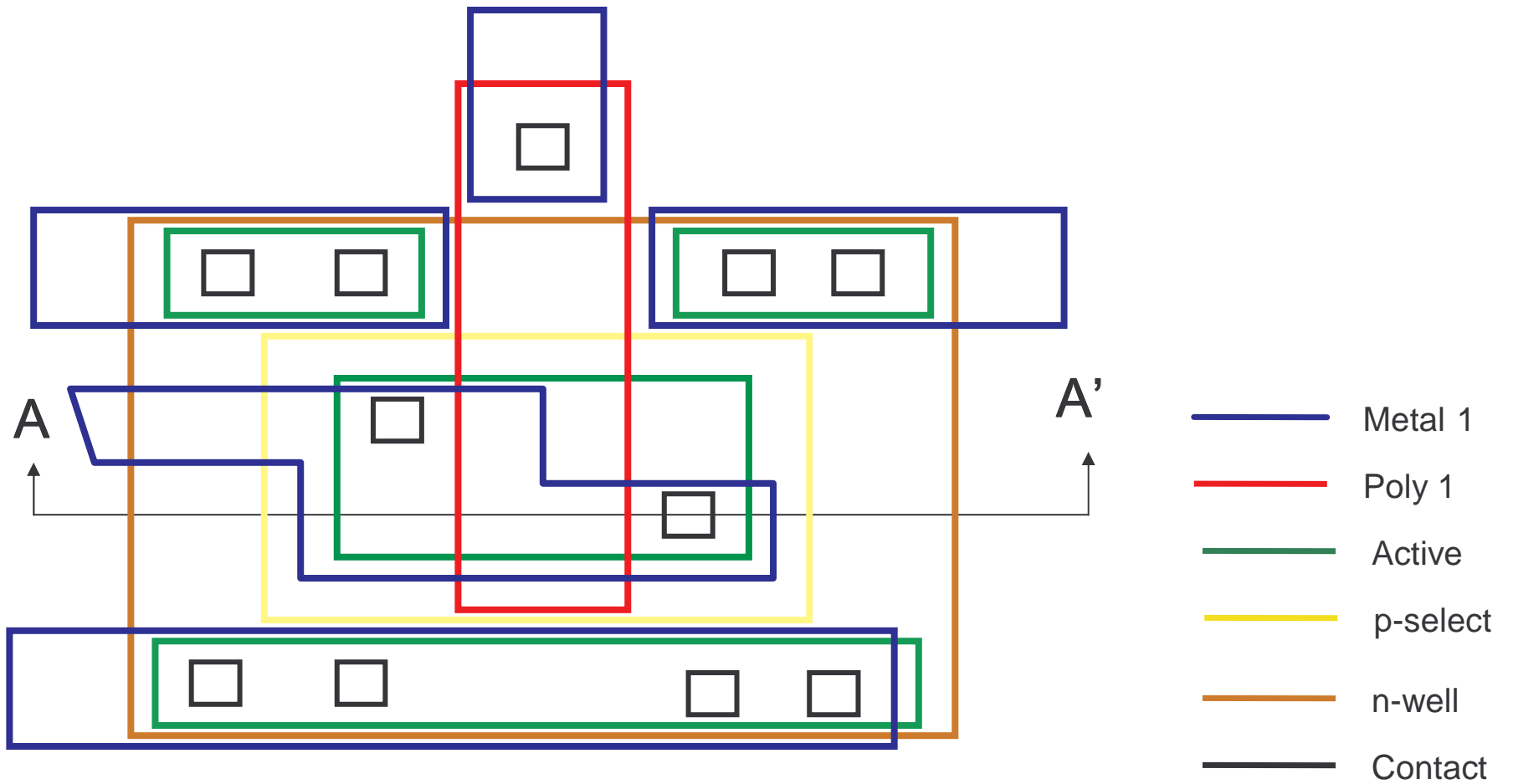
EE 434

Lecture 11

Basic Semiconductor Processes
Devices in Semiconductor Processes

Quiz 9 The top view of a device fabricated in a bulk CMOS process is shown in the figure below

- a) Identify the device
- b) Sketch a cross-section along the AA' section line



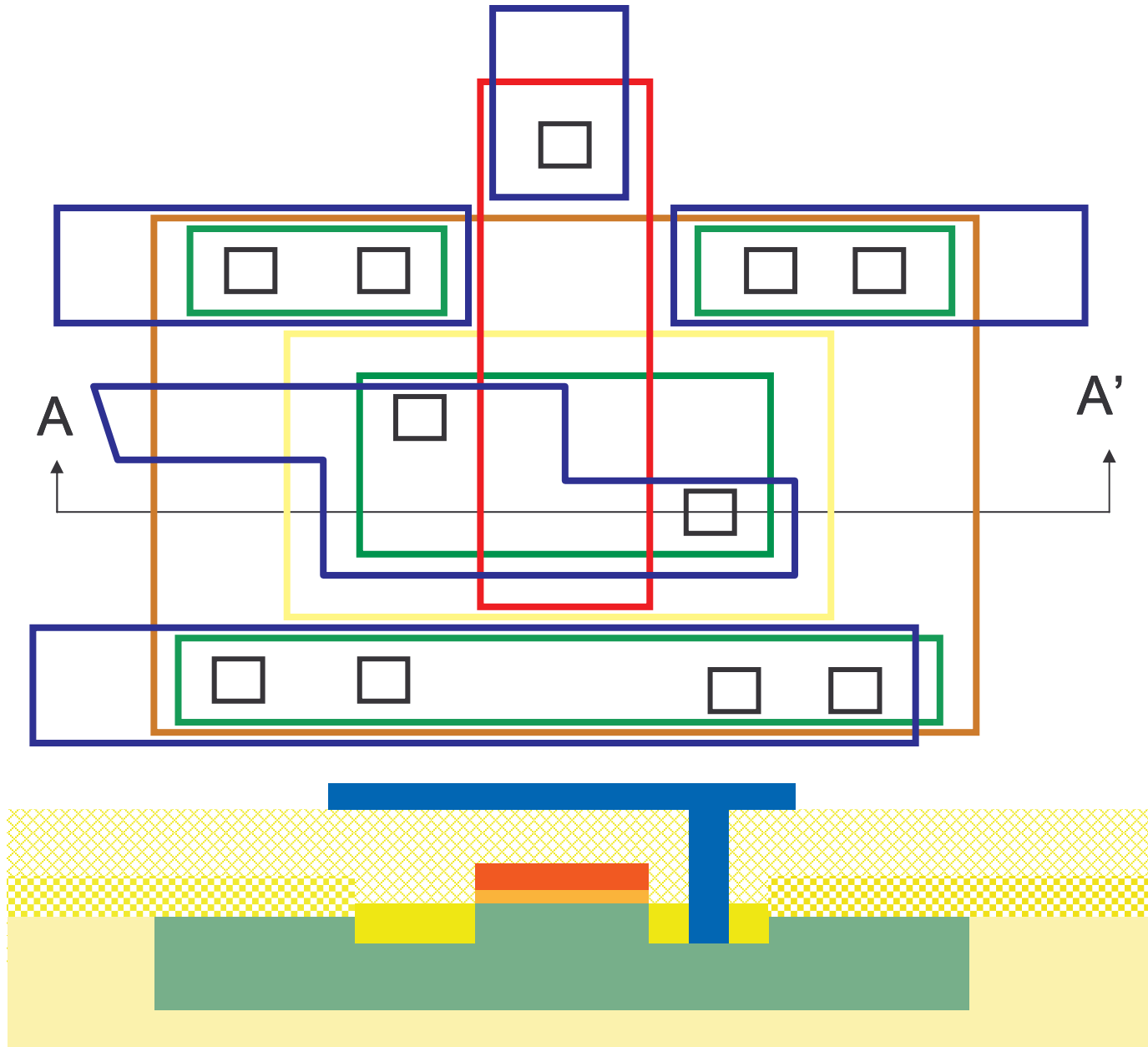
And the number is

1 8 7 5 3
6 9 4 2

1

Quiz 9 Solution

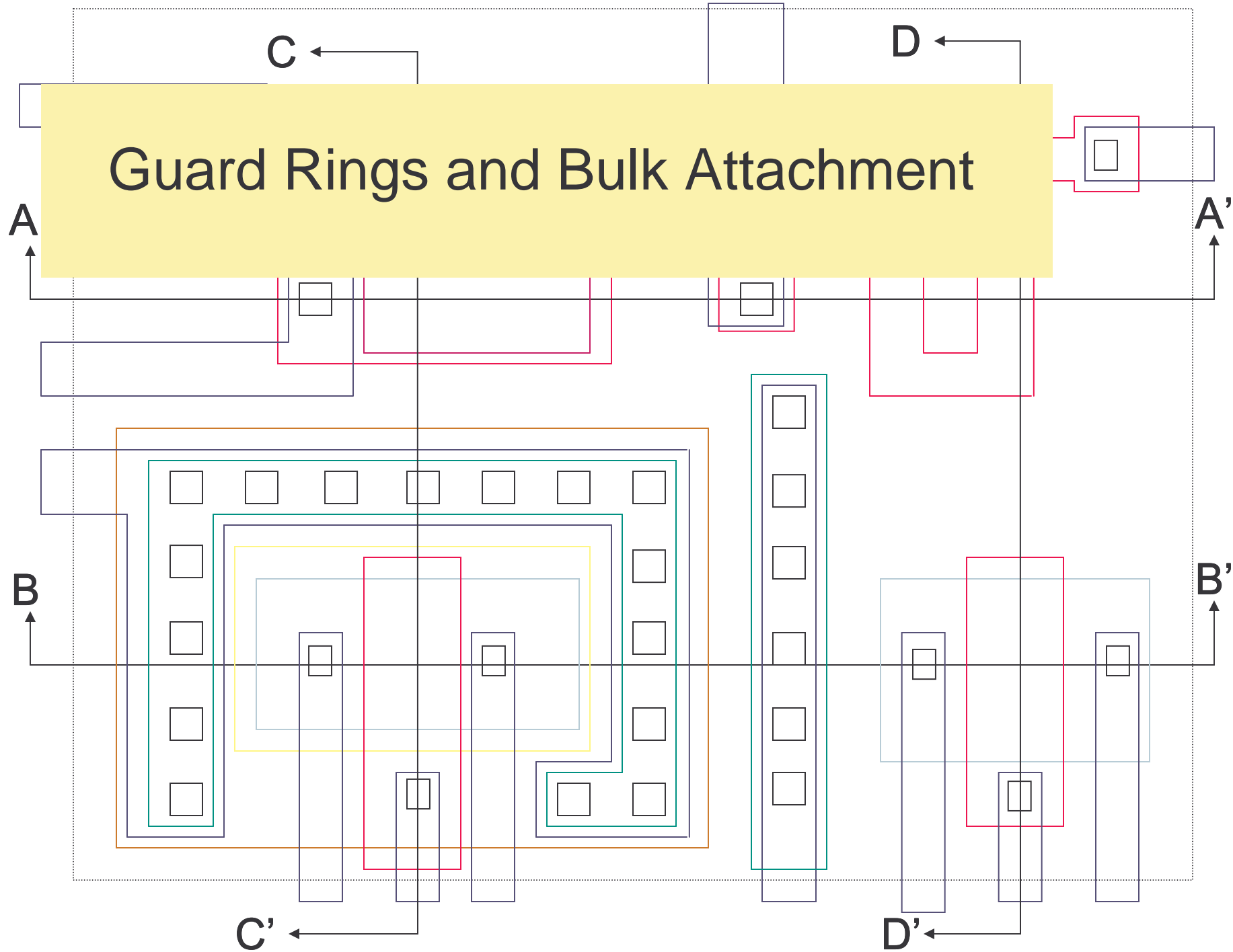
a) p-channel MOS Transistor



Review from Last Time

- Process Flow is a “recipe” for the process
 - Shows what can and can not be made
 - Gives insight into performance capabilities and limitations
- Back-End Processes
 - Die attach options (eutectic, preform,conductive epoxy)
 - Stresses the die
 - Bonding
 - Wire bonding
 - Bump bonding
 - Packaging
 - Many packaging options
 - Package Costs can be large so defective die should be eliminated before packaging

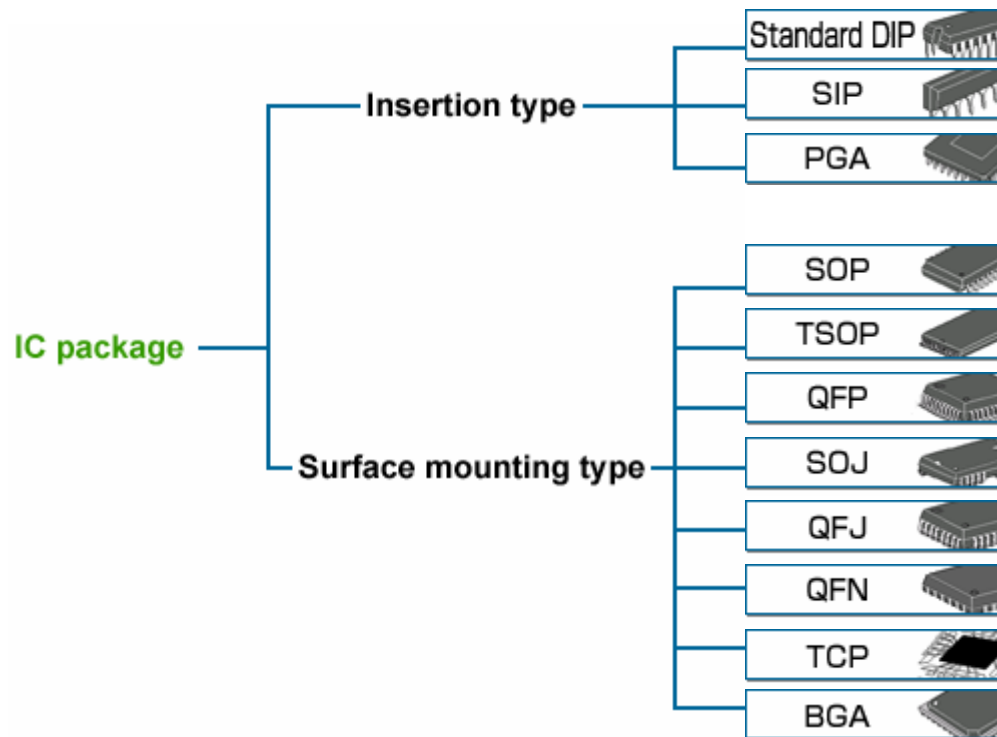
Guard Rings and Bulk Attachment



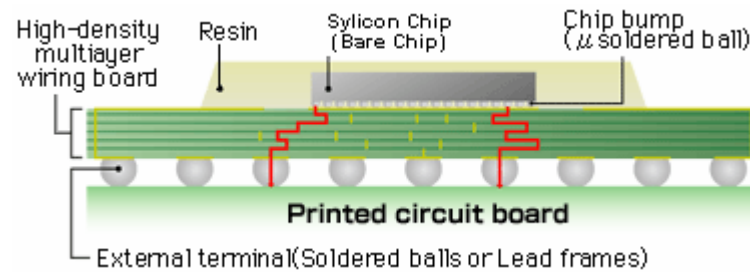
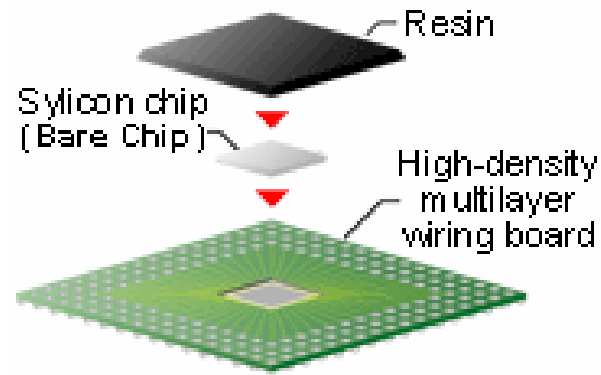
Packaging

1. Many variants in packages now available
2. Considerable development ongoing on developing packaging technology
3. Cost can vary from few cents to tens of dollars
4. Must minimize product loss after packaged
5. Choice of package for a product is serious business
6. Designer invariably needs to know packaging plans and package models

Packaging



Packaging



Basic Semiconductor Processes

MOS (Metal Oxide Semiconductor)

1. NMOS n-ch
 2. PMOS p-ch
 3. CMOS n-ch & p-ch
- Basic Device: MOSFET
 - Niche Device: MESFET
 - Other Devices: Diode
BJT
Resistors
Capacitors
Schottky Diode

Basic Semiconductor Processes

Bipolar

1. T²L
2. ECL
3. I²L
4. Linear ICs
 - Basic Device: BJT (Bipolar Junction Transistor)
 - Niche Devices: HBJT (Heterojunction Bipolar Transistor)
HBT
 - Other Devices: Diode
Resistor
Capacitor
Schottky Diode
JFET (Junction Field Effect Transistor)

Basic Semiconductor Processes

Other Processes

- Thin and Thick Film Processes
 - Basic Device: Resistor
- BiMOS or BiCMOS
 - Combines both MOS & Bipolar Processes
 - Basic Devices: MOSFET & BJT
- SiGe
 - BJT with HBT implementation
- SiGe / MOS
 - Combines HBT & MOSFET technology
- SOI / SOS (Silicon on Insulator / Silicon on Sapphire)
- Twin-Well & Twin Tub CMOS
 - Very similar to basic CMOS but more optimal transistor char.

Summary of Devices by Processes

- Standard CMOS Process
 - MOS Transistors
 - n-channel
 - p-channel
 - Capacitors
 - Resistors
 - Diodes
 - BJT (in some processes)
 - npn
 - pnp
 - JFET (in some processes)
 - n-channel
 - p-channel
- Standard Bipolar Process
 - BJT
 - npn
 - pnp
 - JFET
 - n-channel
 - p-channel
 - Diodes
 - Resistors
 - Capacitors
- Niche Devices
 - Photodetectors (photodiodes, phototransistors, photoresistors)
 - MESFET
 - HBT
 - Schottky Diode (not Shockley)
 - MEM Devices
 -

Basic Devices

- Devices in Standard Processes

- MOS Transistors

- n-channel
- p-channel

- Capacitors

- Resistors

- Diodes

- BJT (in some processes)

- npn
- pnp

**Primary Consideration
in This Course**

**Limited Consideration in
This Course**

- Niche Devices

- Photodetectors

- MESFET

- Schottky Diode (not Shockley)

- MEM Devices

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Basic Devices and Device Models

- Resistor
- Diode
- Capacitor
- MOSFET
- BJT

Basic Devices and Device Models

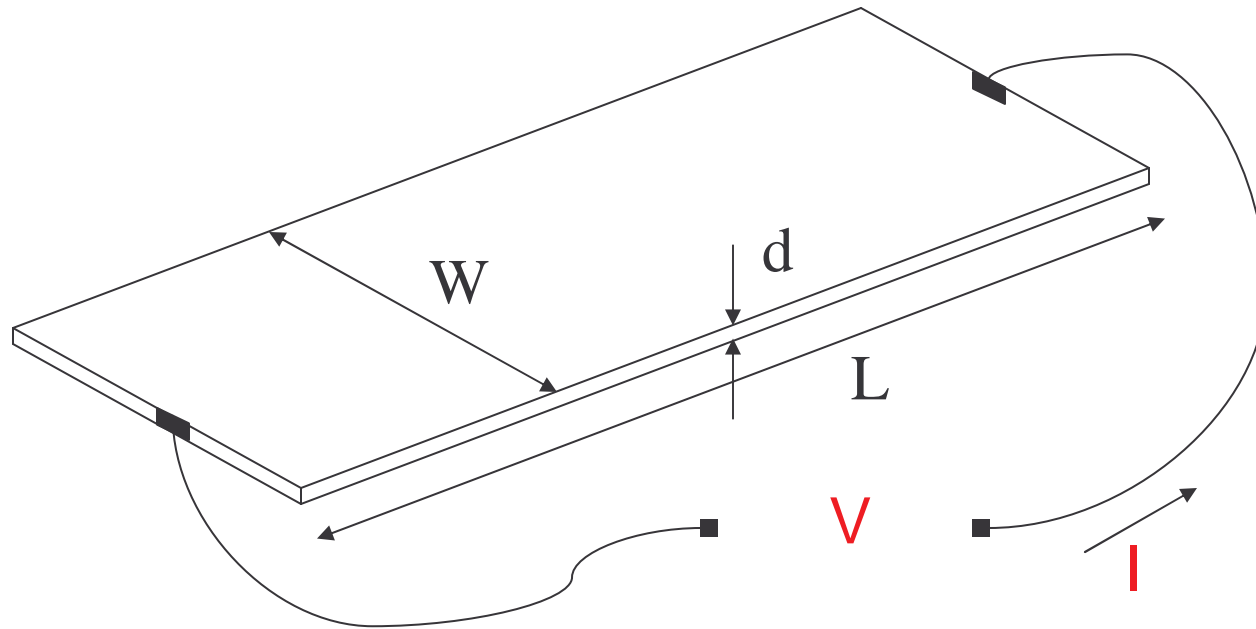
 Resistor

- Diode
- Capacitor
- MOSFET
- BJT

Resistors

- Generally thin-film devices
- Almost any thin-film layer can be used as a resistor
 - Diffused resistors
 - Poly Resistors
 - Metal Resistors
 - “Thin-film” adders (SiCr or NiCr)
- Subject to process variations, gradient effects and local random variations
- Often temperature and voltage dependent
 - Ambient temperature
 - Local Heating
- Nonlinearities often a cause of distortion when used in circuits
- Trimming possible resistors
 - Laser,links,switches

Resistor Model

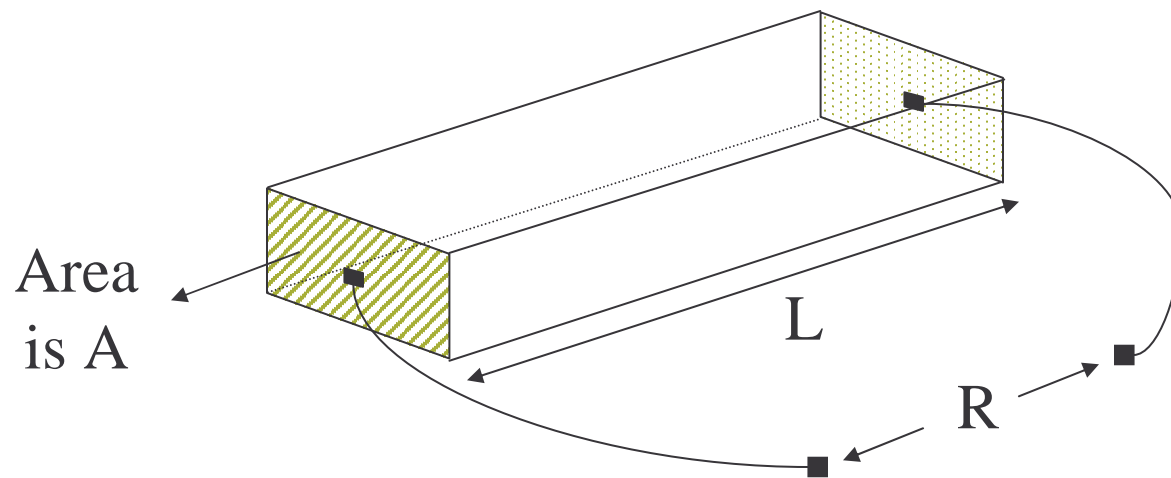


Model:

$$R = \frac{V}{I}$$

Resistivity

- Volumetric measure of conduction capability of a material



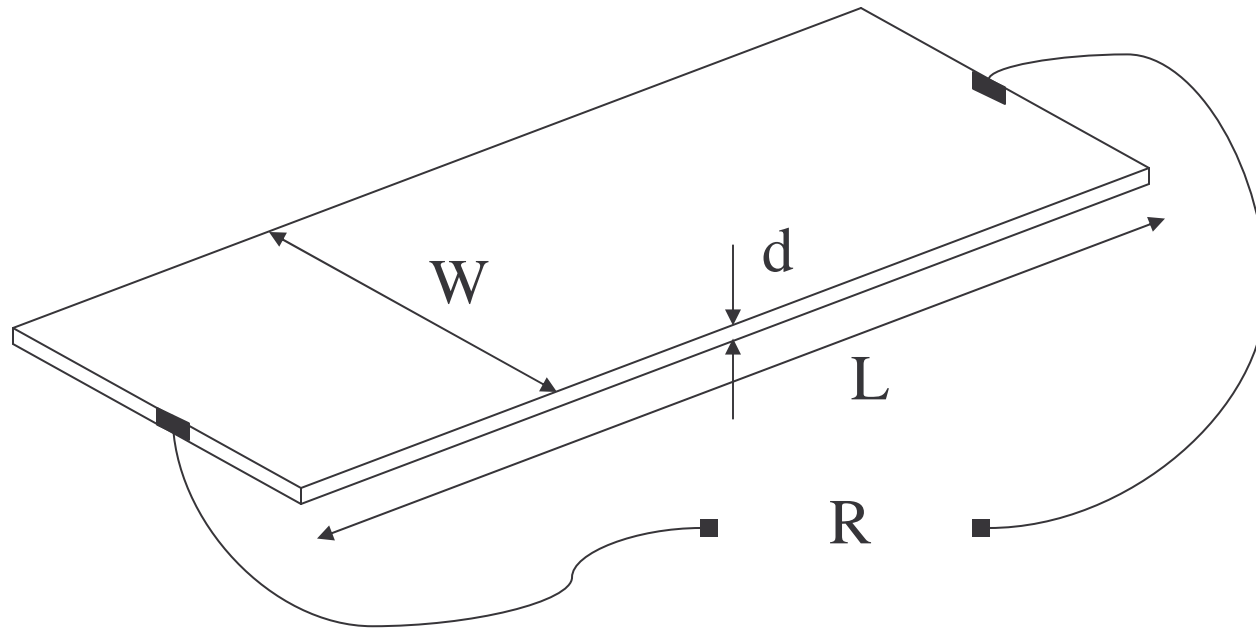
Area
is A

units : ohm cm

$$\rho = \frac{AR}{L}$$

for homogeneous
material,
 $\rho \perp A, R, L$

Sheet Resistance



$$R_{\square} = \frac{RW}{L} \quad (\text{for } d \ll w, d \ll L) \quad \text{units : ohms / } \square$$

for homogeneous materials, R_{\square} is independent of W, L, R

Relationship between ρ and R_{\square}

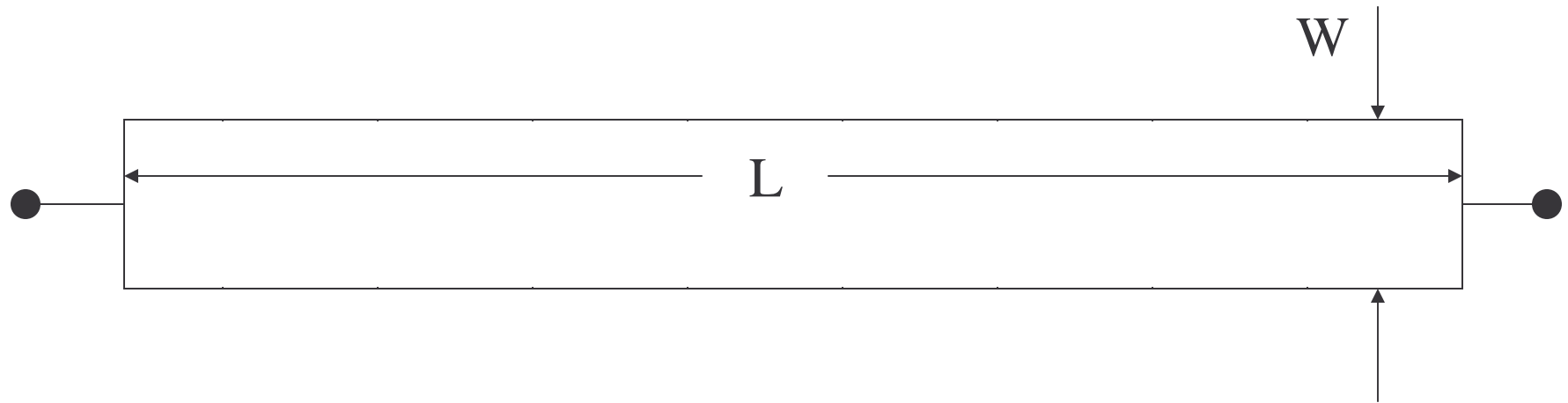
$$\left. \begin{aligned} R_{\square} &= \frac{RW}{L} \\ \rho &= \frac{AR}{L} \end{aligned} \right\} \longrightarrow \begin{aligned} \rho &= \frac{A}{W} R_{\square} \\ A &= W \times d \end{aligned}$$

$$\rho = \frac{A}{W} R_{\square} = \frac{\cancel{W}d}{\cancel{W}} R_{\square} = d \times R_{\square}$$

Number of squares, N_s , often used instead of L / W in determining resistance of film resistors

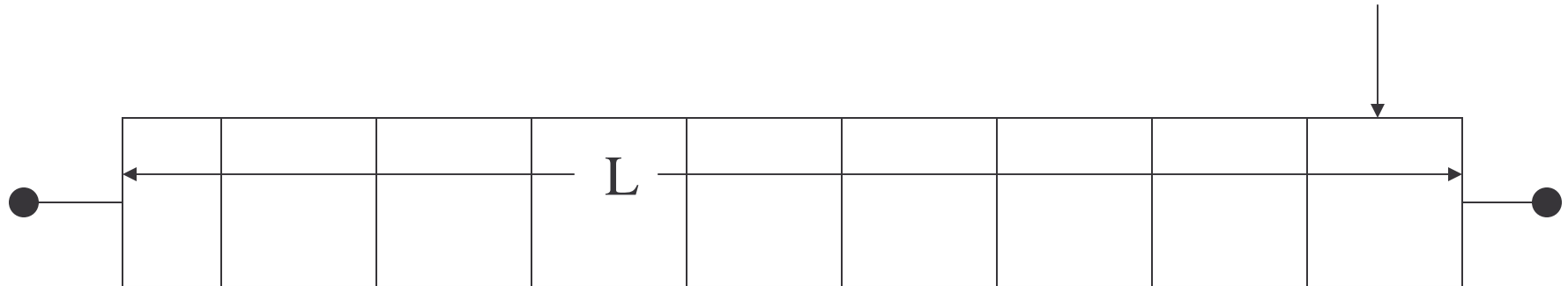
$$R = R_{\square} N_s$$

Example 1



$$R = ?$$

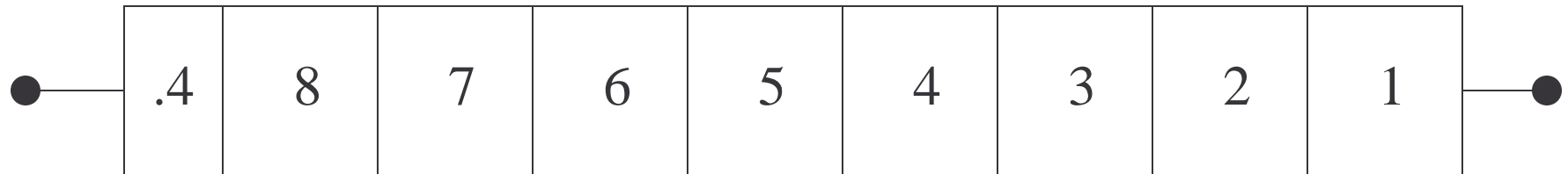
Example 1



$$\frac{L}{W} = N_s$$

W

Example 1



$R = ?$

Example 1



$$R = ?$$

$$N_S = 8.4$$

$$R = R_{\square} (8.4)$$

Corners in Film Resistors



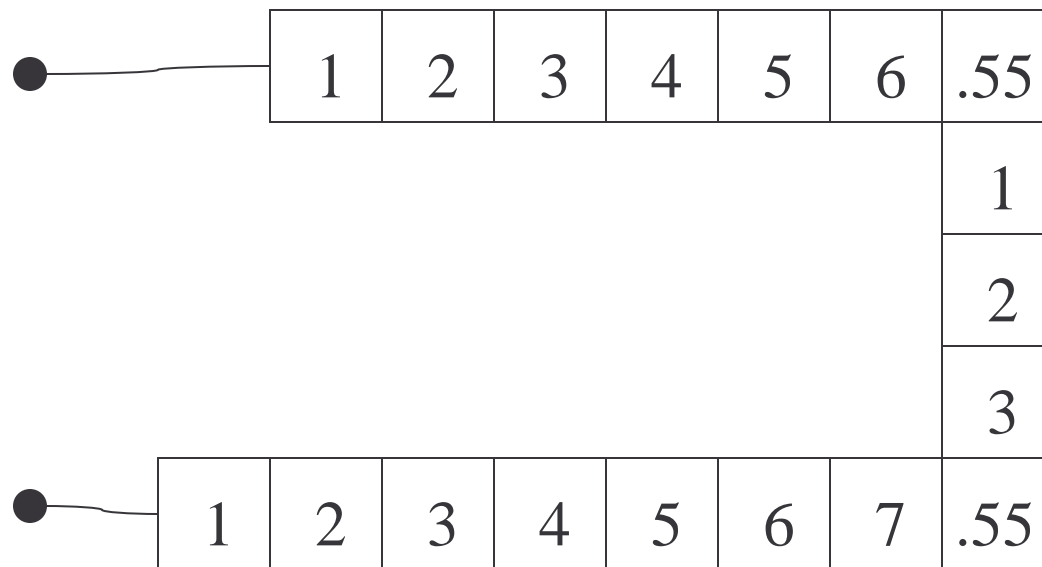
Rule of Thumb: .55 squares for each corner

Example 2

Determine R if $R_1 = 100 \Omega / \square$



Example 2



$$N_s = 17.1$$

$$R = (17.1) R_{\square}$$

$$R = 1710 \Omega$$

Resistivity of Materials used in Semiconductor Processing

- Cu: $1.7E-6 \Omega\text{cm}$
- Al: $2.7E-4 \Omega\text{cm}$
- Gold: $2.4E-6 \Omega\text{cm}$
- Platinum: $3.0E-6 \Omega\text{cm}$
- n-Si: $.25 \text{ to } 5 \Omega\text{cm}$
- intrinsic Si: $2.5E5 \Omega\text{cm}$
- SiO₂: $E14 \Omega\text{cm}$

Temperature Coefficients

Used for indicating temperature sensitivity of resistors & capacitors

For a resistor:

$$\text{TCR} = \left(\frac{1}{R} \frac{dR}{dT} \right) \Bigg|_{\text{op. temp}}^{10^6} \quad \text{ppm}/^\circ\text{C}$$

This diff eqn can easily be solved if TCR is a constant

$$R(T_2) = R(T_1) e^{\frac{T_2 - T_1}{10^6} \text{TCR}}$$

$$R(T_2) \approx R(T_1) \left[1 + (T_2 - T_1) \frac{\text{TCR}}{10^6} \right]$$

Identical Expressions for Capacitors

Voltage Coefficients

Used for indicating voltage sensitivity of resistors & capacitors

For a resistor:

$$\mathbf{VCR} = \left(\frac{1}{R} \frac{dR}{dV} \right) \Bigg|_{\text{ref voltage}}^{10^6} \quad \mathbf{ppm/V}$$

This diff eqn can easily be solved if VCR is a constant

$$\mathbf{R(V_2)} = \mathbf{R(V_1)} e^{\frac{V_2 - V_1}{10^6} \mathbf{VCR}}$$

$$\mathbf{R(V_2)} \approx \mathbf{R(V_1)} \left[1 + (V_2 - V_1) \frac{\mathbf{VCR}}{10^6} \right]$$

Identical Expressions for Capacitors

Temperature and Voltage Coefficients

- Temperature and voltage coefficients often quite large for diffused resistors
- Temperature and voltage coefficients often quite small for poly and metal resistors